

**Amendments to the Specification:**

Please replace the paragraph beginning on page 4, line 20 with the following rewritten paragraph:

Turning now to the drawings, and more particularly to FIGS. 1A and 1B, polishing element 10 of the first embodiment of the invention is illustrated. According to FIGS. 1A and 1B, polishing element 10 has a substantially rigid support member 12 with an outer perimeter 14 for cooperatively associating with a tool, such as the exemplary rotary tool shown in Fig. 10. The outer perimeter 14 terminates at one end with a mounting surface 16 provided for affixing a compliant polishing member or pad 18. Compliant polishing member 18 may be affixed to mounting surface 16 in any number of ways including gluing, friction or interference fit, or with a screw. In addition, compliant polishing member 18 may be mounted to a substantially rigid support member 12 using a variety of techniques including chemical bonding and thermal bonding. Moreover, the compliant polishing member 18 may be molded to the mounting surface 16.

Please replace the paragraph beginning on page 4, line 30 with the following rewritten paragraph:

Referring to FIGS 1A, 1B and 2, polishing tool 26 comprises a polishing fluid applicator or nozzle 23 and the polishing element 10 (compliant polishing member 18 only illustrated) in a precision surface polishing application, for example, polishing an aspheric optical surface 22. Compliant polishing member 18 of the invention has a plurality of regularly spaced polishing portions or lobes 20 for spreading polishing fluid 21 across the surface 22 to be polished. In another embodiment, the lobes 20 may be squared to form a polygonal shape. The recess 24 between nearest adjacent lobes 20 enables a predetermined amount of polishing fluid 21 to be spread in a predictable manner across the surface 22 to be polished. During a precision polishing application, the polishing element 10 is structurally mounted into a spindle (not shown) of a rotary device (FIG. 11) via the substantially rigid support member 12 (FIGS. 1A and 1B). The polishing element 10 is rotated while in compressive contact with the surface 22 to be polished. A polishing fluid, such as a slurry of abrasive particles, is disposed, typically via nozzle 23, in an interfacial area between adjacent lobes 20 of the

compliant polishing element 10 and the surface 22 to be polished. As the polishing element 10 is rotated by the rotary device, the plurality of spaced polishing portions or lobes 20 traps polishing fluid 21 between the surface 22 to be polished and the nearest of the lobes 20. This action forces the polishing fluid 21 across the surface 22 to be polished. In the process, it also prevents polishing fluid starvation from any area on the surface 22 to be polished.